

***** Welcome to STN International *****

NEWS 1 Web Page URLs for STN Seminar Schedule - N. America
 NEWS 2 "Ask CAS" for self-help around the clock
 NEWS 3 SEP 09 CA/Caplus records now contain indexing from 1907 to the present
 NEWS 4 AUG 05 New pricing for EUROPATFULL and PCTFULL effective August 1, 2003
 NEWS 5 AUG 13 Field Availability (/FA) field enhanced in BEILSTEIN
 NEWS 6 AUG 18 Data available for download as a PDF in RDISCLOSURE
 NEWS 7 AUG 18 Simultaneous left and right truncation added to PASCAL
 NEWS 8 AUG 18 FROSTI and KOSMET enhanced with Simultaneous Left and Right Truncation
 NEWS 9 AUG 18 Simultaneous left and right truncation added to ANABSTR
 NEWS 10 SEP 22 DIPPR file reloaded
 NEWS 11 SEP 25 INPADOC: Legal Status data to be reloaded
 NEWS 12 SEP 29 DISSABS now available on STN
 NEWS 13 OCT 10 PCTFULL: Two new display fields added

NEWS EXPRESS OCTOBER 01 CURRENT WINDOWS VERSION IS V6.01a, CURRENT MACINTOSH VERSION IS V6.0b(ENG) AND V6.0Jb(JP), AND CURRENT DISCOVER FILE IS DATED 23 SEPTEMBER 2003

NEWS HOURS STN Operating Hours Plus Help Desk Availability
 NEWS INTER General Internet Information
 NEWS LOGIN Welcome Banner and News Items
 NEWS PHONE Direct Dial and Telecommunication Network Access to STN
 NEWS WWW CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that specific topic.

All use of STN is subject to the provisions of the STN Customer agreement. Please note that this agreement limits use to scientific research. Use for software development or design or implementation of commercial gateways or other similar uses is prohibited and may result in loss of user privileges and other penalties.

***** STN Columbus *****

FILE 'HOME' ENTERED AT 06:47:29 ON 13 OCT 2003

=> file inspec		
COST IN U.S. DOLLARS	SINCE FILE	TOTAL
	ENTRY	SESSION
FULL ESTIMATED COST	0.21	0.21

FILE 'INSPEC' ENTERED AT 06:47:39 ON 13 OCT 2003
 Compiled and produced by the IEE in association with FIZ KARLSRUHE
 COPYRIGHT 2003 (c) INSTITUTION OF ELECTRICAL ENGINEERS (IEE)

FILE LAST UPDATED: 13 OCT 2003 <20031013/UP>
 FILE COVERS 1969 TO DATE.

<<< SIMULTANEOUS LEFT AND RIGHT TRUNCATION AVAILABLE IN
 THE BASIC INDEX >>>

=> s phase shift mask
 713679 PHASE
 147036 SHIFT
 21527 MASK
 L1 516 PHASE SHIFT MASK
 (PHASE(W)SHIFT(W)MASK)

=> s exposure optical system
 61904 EXPOSURE

668960 OPTICAL
1595550 SYSTEM

L2 1 EXPOSURE OPTICAL SYSTEM
(EXPOSURE(W)OPTICAL(W)SYSTEM)

=> d 13

L2 ANSWER 1 OF 1 INSPEC (C) 2003 IEE on STN

Full Text	References
--------------	------------

AN 2001:6804707 INSPEC DN B2001-02-2550G-151
TI Influence of electron density distribution at the electron source in a projection exposure system.
AU Kotera, M.; Sakai, M. (Osaka Inst. of Technol., Japan); Shimizu, I.; Tomo, Y.; Yoshida, A.; Kojima, Y.; Yamabe, M.
SO Digest of Papers Microprocesses and Nanotechnology 2000. 2000 International Microprocesses and Nanotechnology Conference (IEEE Cat. No.00EX387) Tokyo, Japan: Japan Soc. Appl. Phys. 2000. p.140-1 of xxviii+306 pp. 0 refs.
Conference: Tokyo, Japan, 11-13 July 2000
Sponsor(s): Japan Soc. Appl. Phys.; IEEE Electron Device Soc.; American Vacuum Soc.; Assoc. Super-Adv. Electron. Technol.; IEE of Japan; IEICR; Japanese Soc. Synchrotron Radiation Res.; Japanese Soc. Electron Microscopy; Surface Sci. Soc. Japan; Vacuum Soc. Japan
ISBN: 4-89114-004-6
DT Conference Article
TC Theoretical
CY Japan
LA English

=> 3 EXCAVATION

L3 871 EXCAVATION

=> 11 and 12

L4 0 L1 AND L2

=> 11 and 13

L5 0 L1 AND L3

=> 6 RESIST PATTERN

12602 RESIST
182954 PATTERN
L6 424 RESIST PATTERN
(RESIST(W)PATTERN)

=> 11 and 16

L7 7 L1 AND L6

=> 17 1-7

L7 ANSWER 1 OF 7 INSPEC (C) 2003 IEE on STN

Full Text	References
--------------	------------

AN 2003:7717431 INSPEC DN B2003-10-2550G-142
TI Preliminary study of 65 nm node alternating **phase-shift mask** fabrication.
AU Hosono, K.; Ishiwata, N.; Asai, S.; Maruyama, H.; Miyahara, Y. (Fujitsu Ltd., Tokyo, Japan); Sanki, S.; Yamashita, Y.; Hotta, Y.; Furukawa, T.; Naitou, M.; Miyashita, H.; Noguchi, S.
SO Proceedings of the SPIE - The International Society for Optical Engineering (2002) vol.4889, p.1273-80. 3 refs.
Published by: SPIE-Int. Soc. Opt. Eng
Price: CCCC 0277-786X/02/\$15.00

CODEN: PSISDG ISSN: 0277-786X
 SIC1: 0277-786X(2002)4889L.1273:PSNA;1-Y
 Conference: 22nd Annual BACUS Symposium on Photomask Technology. Monterey,
 CA, USA, 1-4 Oct 2002
 Sponsor(s): SPIE

DT Conference Article; Journal
 TC Experimental
 CY United States
 LA English

L7 ANSWER 2 OF 7 INSPEC (C) 2003 IEE on STN

Full
 Text

AN 1998:5803277 INSPEC DN B9802-2550G-201
 TI Optical proximity correction of alternating phase-shift masks for 0.18 μ m KrF lithography.
 AU Yasuzato, T.; Ishida, S. (ULSI Device Dev. Lab., NEC Corp., Sagamihara, Japan); Shioiri, S.; Tanabe, H.; Kasama, K.
 SO Proceedings of the SPIE - The International Society for Optical Engineering (1997) vol.3051, p.751-62. 5 refs.
 Published by: SPIE-Int. Soc. Opt. Eng
 Price: CCCC 0277-786X/97/\$10.00
 CODEN: PSISDG ISSN: 0277-786X
 SIC1: 0277-786X(1997)3051L.751:OPCA;1-0
 Conference: Optical Microlithography X. Santa Clara, CA, USA, 12-14 March 1997
 Sponsor(s): SPIE
 DT Conference Article; Journal
 TC Experimental
 CY United States
 LA English

L7 ANSWER 3 OF 7 INSPEC (C) 2003 IEE on STN

Full
 Text

AN 1997:5611672 INSPEC DN B9708-2550G-008
 TI Impact of lens aberrations on optical lithography.
 AU Brunner, T.A. (Microelectron. Div., IBM Corp., East Fishkill, NY, USA)
 SO IBM Journal of Research and Development (Jan.-March 1997) vol.41, no.1-2, p.57-67. 18 refs.
 Published by: IBM
 Price: CCCC 0018-8646/97/\$5.00
 CODEN: IBMJAE ISSN: 0018-8646
 SIC1: 0018-8646(199701/03)41:1/2L.57:ILAO;1-N
 DT Journal
 TC Theoretical
 CY United States
 LA English

L7 ANSWER 4 OF 7 INSPEC (C) 2003 IEE on STN

Full
 Text

AN 1996:5426662 INSPEC DN B9701-2550G-005; C9701-7410D-002
 TI Improvement of **resist pattern** fidelity with partial attenuated **phase shift mask**.
 AU Yasuzato, T.; Ishida, S.; Kasama, K. (VLSI Dev. Div., NEC Corp., Sagamihara, Japan)
 SO Proceedings of the SPIE - The International Society for Optical Engineering (1996) vol.2726, p.496-507. 12 refs.
 Published by: SPIE-Int. Soc. Opt. Eng
 Price: CCCC 0 8194 2102 2/96/\$6.00
 CODEN: PSISDG ISSN: 0277-786X
 SIC1: 0277-786X(1996)2726L.496:IRPF;1-Q
 Conference: Optical Microlithography IX. Santa Clara, CA, USA, 13-15 March

1996

Sponsor(s): SPIE
DT Conference Article; Journal
TC Practical; Theoretical; Experimental
CY United States
LA English

L7 ANSWER 5 OF 7 INSPEC (C) 2003 IEE on STN

Full
Text

AN 1995:5082029 INSPEC DN B9512-2550G-016
TI A study of optical proximity effects using off-axis illumination with attenuated **phase shift mask**.
AU Ahn, C.-N.; Baik, K.-H.; Lee, Y.-S.; Kim, H.-E.; Hur, I.-B.; Kim, Y.-S.; Kim, J.-H.; Choi, S.-H. (Semicond. R. & D. Labs., Hyundai Electron. Ind. Co. Ltd., Kyungki-do, South Korea)
SO Proceedings of the SPIE - The International Society for Optical Engineering (1995) vol.2440, p.222-39. 7 refs.
Price: CCCC 0 8194 1788 2/95/\$6.00
CODEN: PSISDG ISSN: 0277-786X
Conference: Optical/Laser Microlithography VII. Santa Clara, CA, USA, 22-24 Feb 1995
Sponsor(s): SPIE
DT Conference Article; Journal
TC Practical; Theoretical; Experimental
CY United States
LA English

L7 ANSWER 6 OF 7 INSPEC (C) 2003 IEE on STN

Full
Text

AN 1995:4968479 INSPEC DN B9507-2550G-035
TI Poly(cyclohexyl 2-cyanoacrylate-co-ethoxyethyl 2-cyanoacrylate) as a positive tone electron beam resist for **phase-shift mask** fabrication.
AU Tamura, A.; Yonezawa, M. (Electron. Res. Lab., Toppan Printing Co. Ltd., Saitama, Japan); Sato, M.; Okuyama, T.
SO Proceedings of the SPIE - The International Society for Optical Engineering (1994) vol.2254, p.228-36. 4 refs.
Price: CCCC 0 8194 1563 4/94/\$6.00
CODEN: PSISDG ISSN: 0277-786X
Conference: Photomask and X-Ray Mask Technology. Kanagawa, Japan, 22 April 1994
Sponsor(s): SPIE; BACUS
DT Conference Article; Journal
TC Practical; Experimental
CY United States
LA English

L7 ANSWER 7 OF 7 INSPEC (C) 2003 IEE on STN

Full
Text

AN 1992:4311819 INSPEC DN B9302-2550G-046
TI Resolution improvement with annular illumination.
AU Tounai, K.; Tanabe, H.; Nozue, H.; Kasama, K. (VLSI Dev. Div., NEC Corp., Kanagawa, Japan)
SO Proceedings of the SPIE - The International Society for Optical Engineering (1992) vol.1674, pt.2, p.753-64. 5 refs.
Price: CCCC 0 8194 0829 8/92/\$4.00
CODEN: PSISDG ISSN: 0277-786X
Conference: Optical/Laser Microlithography V. San Jose, CA, USA, 11-13 March 1992
Sponsor(s): SPIE
DT Conference Article; Journal
TC Practical; Experimental

CY United States
LA English

=>